



SHEET 1 OF 1

INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION

(PTO-1449)

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**050212-0559**SERIAL NO.  
**10/774,417**APPLICANT  
**Yosihki NISHIBAYASHI, et al.**FILING DATE  
**February 10, 2004**GROUP  
**1763**

## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code(s) (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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## FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation Yes No

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
AWO		Hong J. et al, "Etching process of hydrogenated amorphous carbon (a-C:H) thin films in a dual ECR-r.f. nitrogen plasma", vol. 8, no. 2-5, March 1999, pages 572-576, XP004364947
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AWO		Valyi G. et al, "Analysis of chemical processes of plasma etching", vol. 76, no. 3, 13 February 1981, pages 215-219, XP002381595
AWO		Search Report dated June 21, 2006

EXAMINER  
/Allan Olsen/DATE CONSIDERED  
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